

IN THE ABSTRACT:

Please cancel the current abstract and insert the following.

~~When an exposure shot region cannot converge to a predetermined focus precision while a substrate is scanned, the exposure shot is determined as an error. A wafer stage controller (101) for controlling a shot beam from a pulse laser source (116) stops emission of the pulse laser source (116) if a non-exposure focus error is determined, and executes forced exposure to completely expose the remaining portion of the exposure shot region if an exposure abort focus error is determined.~~

-- A scanning exposure apparatus for exposing a substrate to a pattern includes an exposure system which exposes the substrate to the pattern with respect to a unit region of the substrate to which the pattern is transferred, a determination system which determines whether a condition of an exposure performed by the exposure system is allowable during the exposure, and a control system which causes the exposure system to continue exposing a remaining region in the unit region of the substrate to the pattern, even after the determination system makes a negative determination for the unit region. --